



Session Title:	[TuF1] Nano Thin Film Deposition I
Session Date:	November 12 (Tue.), 2024
Session Time:	13:00-14:40
Session Room:	Room F (Ballroom, 5F, Grand Josun Busan)
Session Chair:	Prof. Woo Hee Kim (Hanyang Univ., Korea)

[TuF1-1] [Plenary]

13:00-13:45

New Mechanisms for Metal Thermal Atomic Layer Etching

Steven George (Univ. of Colorado, USA)

[TuF1-2] [Invited]

13:45-14:15

Surface Reaction Mechanisms of SiN ALD Analyzed with Atomic-Scale Simulations

Abdullah Y. Jaber, Jomar U. Tercero, Tomoko Ito, Kazuhiro Karahashi, Kazumasa Ikuse, Michiro Isobe, and Satoshi Hamaguchi (Osaka Univ., Japan)

[TuF1-3] [Invited]

14:15-14:40

Surface Adsorption/Desorption Reactions and Precursor Design for ALD/ALE

Sang-Ick Lee, Sangyong Jeon, Taeseok Byun, Yonghee Kwon, and Sangchan Lee (DNF Co., Ltd., Korea)